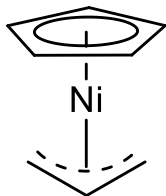


Catalog # 28-0009 Allyl(cyclopentadienyl)nickel(II), min. 97%



Thermal Behavior:

- Vapor pressure 10 Torr at 73 °C [1], 0.84 Torr at 30 °C [3]
- TGA available in [1]
- Melting point: 9 °C [1]

Technical Notes:

1. Volatile liquid precursor for the growth of Nickel metal and oxide films by CVD

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ni	CVD	25 °C	75-300 Torr	H ₂	80-200 °C	[1, 2]
NiO	CVD	30 °C	760 Torr	O ₂	300-600 °C	[3]

References:

1. [J. Cryst. Growth 2005, 275, e1115](#)
2. [J. Cryst. Growth 2005, 275, e1121](#)
3. [J. Cryst. Growth 2016, 451, 57](#)